



Industrial Instruments General Brochure

The highly cost-effective SMZ series offer outstanding optical performance, flexible system expandability, and superb operability.

		Parallel Optics Type										
			SMZ1270	CM7000N								
	SMZ25	SMZ18	SMZ1270i	SMZ800N								
Zoom Ratio	25 : 1	18 : 1	12.7 : 1	8:1								
Zoom Range	0.63–15.75×	0.75–13.5×	0.63-8×	1–8×								
Total Magnification*1 (Standard combination*2)	3.15-945× (6.3-157.5×)	3.75-810× (7.5-135×)	3.15-480× (6.3-80×)	5–480× (10–80×)								
WD *3	60 mm	60 mm	60 mm 70 mm									
Camera	V	V	✓	V								

	Greenough Type											
	SMZ745 SMZ745T		SMZ SMZ		SMZ-2							
Zoom Ratio	7.5 : 1		4.4 : 1	4.3 : 1		5 : 1						
Zoom Range	0.67–5×		0.8 –3.5×	0.7 –3×		0.8-4×						
Total Magnification*1 (Standard combination*2)	3.35-300× (6.7-50×)		4–70× 3.5–60× (7–30×)			4–120× (8–40×)						
WD *3	115 mm		100	mm		77.5 mm						
Camera	✓ (SMZ745T only)		_	_								

 $^{^*}$ 1: Depending on combination of Eyepiece and Objective lens. * 2: Combination of Eyepiece $10\times$ and Objective lens $10\times$. * 3: Objective lens $1\times$ or no Auxiliary lens.

Stereo Microscopes Parallel Optics Type - SMZ25 / SMZ18 / SMZ1270 / SMZ1270i / S	M7800NI
Greenough Type - SMZ745 / SMZ745T / SMZ445 / SMZ460 /	
Industrial Microscopes	4-5
Upright Microscopes - LV100ND / LV100NDA / LV100NDA / LV100NDA / LV100NDA / LV100NDA / LV100NPOL / Ci POL Polarizing Microscopes - LV100NPOL / Ci POL	50N / LV150NA / LV150NL / L200N / L200ND / L300N / L300ND
Digital Cameras for Microscopes	6
Microscope Camera – Digital Sight 1000 Microscope Camera – DS-Fi3	Microscope Camera – DS-Ri2 Imaging Software – NIS-Elements L/D/Ar/Br
Optical Interferometric Microscope	•
Optical Interferometric Microscope Systems – BW-S500 / BW-D	buu Series
Objective Lenses Objective Lenses - CFI60-2 / CFI60	8
For Incorporation into Microscopes	
Modular Focusing Units – IM-4 / LV-IM / LV-FM / LV-FMA Dynamic Auto-Focus Unit – LV-DAF	Compact Reflected Microscopes – CM Series Wafer Loaders – NWL200 Series
CNC Video Measuring Systems	10-11
CNC Video Measuring Systems - iNEXIV VMA Series / CNC Confocal Video Measuring Systems - NEXIV VMZ-K Series	NEXIV VMZ-R Series
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Profile Projectors / Data Processing Profile Projectors -V-12B / V-20B	Systems 13 Data Processor - DP-E1A
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Autocollimators / DIGIMICRO Autocollimators - 6B-LED / 6D-LED	14 DIGIMICRO - MF-1001 / MF-501 / MH-15M
Optical Flat / Optical Parallal / Stan	dard 300 mm Scale 15
Optical Flat / Optical Parallel / Stan	uaru ooo miii ocale 13

Please refer to individual product brochures for further details.

Nikon's Industrial Microscopes utilize the CFI60-2 optical system, highly evaluated for providing a high NA combined with long WD.

Upright Microscopes (General model)

LV100ND LV100NDA

Model offers various observation methods with reflected/transmitted illumination.



LV150N LV150NA LV150NL*

Stand and illumination units are selectable according to observation methods and purpose of use.



		Di	_ D1		' -
	EPI	V	V	V	V
Observation Method	EPI (LED)	V	V	V	_
	DIA	V	V	V	_

✓ : Available / — : Not available / △: Simple polarizing observation

Episcopic / Diascopic

01---

Illuminator

- 3×2 Stage (stroke 75×50mm)
- 6×4 Stage (stroke 150×100mm)
- *See the "LV-N Series" brochure for other compatible stages.

	BF	DF	DIC	FL	POL	2-Beam
EPI	V	V	V	V	V	/
EPI (LED)	~	~	V	_	Δ	_

- ✓ : Available / : Not available / Δ: Simple polarizing observation
- Episcopic
- 3×2 Stage (stroke 75×50mm)
- 6×6 Stage (stroke 150×150mm)
- *See the "LV-N Series" brochure for other compatible stages.

BF: Brightfield DF: Darkfield DIC: Differential Interference Contrast FL: Fluorescence POL: Polarizing 2-Beam: Two-Beam Interferometry Ph-C: Phase-Contrast *Only BF, DIC, and S-POL are available for LV150NL

Upright Microscopes (Large-sized stage model)

L200N L200ND

Stage with stroke 200×200mm is available. Suitable for ø200mm wafer observation.



L300N L300ND

Stage with stroke 350×300mm is available. Suitable for ø300mm wafer observation.



Observ Method		EPI DIA *L200N	BF	DF ✓ —	DIC ✓ — ✓: Avai	S-POL	FL * - Not available		EF DI *L30	PI A	BF	DF ✓ —	DIC ✓ — ✓: Ava	S-POL	FL V Not available	
Illumin	ator		200ND : Episcopic / Diascopic						L300N : Episcopic L300ND : Episcopic / Diascopic							
Stage		• 8×8	8×8 Stage (stroke: 200×200mm)					• 14	1×12	2 Stage	(stroke: 3	50×300m	nm)			
									(

BF: Brightfield DF: Darkfield DIC: Differential Interference Contrast S-POL: Simple Polarizing FL: Fluorescence

Inverted Metallurgical Microscopes

MA100N

MA100N is compact, inverted microscopes designed for brightfield and simple polarizing observations.



MA200

With its unique, solid-box structure, the MA200 offers high stability, durability, and a smaller footprint than conventional models.



	BE DE S-POL DIC EL BE DE S-POL DIC EL											E1				
		BF	DF	S-POL	DIC	FL			BF	DF	S-POL	DIC	FL			
Observation	EPI	V		~	_	_		EPI	~	~	/	V	Δ			
Method	✓: Available / —: Not available *Dedicated reflected illumination models.							\checkmark : Available / — : Not available \triangle : Only available with Halogen Lamp and Fiber Illumination *DIA illuminator is available for transmitted light observation.								
Illuminator	• Epi	Episcopic						Episcopic / Diascopic								
Stage	MA-SR-N Rectangular 3-plate Stage N (stroke 50×50mm) MA-SP-N Plain Stage N TS2-S-SM Mechanical Stage CH (stroke 126×78mm) *Please use in combination with MA-SP-N Plain stage N.							MA2-SR Mechanical Stage (stroke 50×50mm)								

BF: Brightfield DF: Darkfield DIC: Differential Interference Contrast S-POL: Simple Polarizing FL: Fluorescence

Polarizing Microscopes

LV100NPOL

Outstanding optical performance, perfect for a wide variety of imaging applications and polarizing techniques.



Ci POL

Compact polarizing microscope that balances optical performance and ease of use.



		BF POL				BF	POL			
Observation	EPI	V	✓		EPI	V	~			
Method	DIA	DIA V			DIA	V	~			
		✓ : Available / — : Not available				V	: Available / : No	ot available		
Illuminator	Episcopic/ Diascopic				Episcopic/ Diascopic					
Stage	High precision rotating stage for polarizing observation				Rotating stage with stage clamp					

BF: Brightfield POL: Polarizing DF: Darkfield DIC: Differential Interference Contrast S-POL: Simple Polarizing FL: Fluorescence

Please refer to individual product brochures for further details.

Digital Sight Series

Microscope Camera

Digital Sight 1000 NEW

Equipped with a 2 megapixel CMOS image sensor, it can capture full HD microscope images. By connecting a microscope to this camera and HDMI monitor, movies and images can be captured and saved onto a pre-inserted SD card in the camera.



Full HD





Three main features of the previous models, high-resolution, high sensitivity and low noise, and highspeed live display are offered in 1



DS-Ri2

Capable of expressing images as is, this microscope digital camera offers high resolution, color reproduction, and frame rate



-45
Militain On-real

Frame Rate	30 fps (1920×1080)	30 fps (1440×1024)	45 fps (1636×1088)
Max Recordable Pixels	1920×1080	2880×2048	4908×3264

Imaging software NIS-Elements

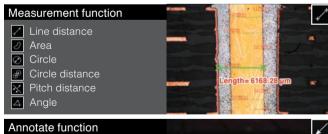
Using a tablet PC

Simply installing NIS-Elements L on a tablet PC enables setting and control of Digital Sight 1000/DS-Fi3/DS-Ri2



A wide variety of tools

NIS-Elements L enables the conducting of simple measurements on images, with input of lines and comments. These can also be written onto and saved with the image, and measurement data can be output.





Scene Mode

Ten camera setting patterns for optimal color reproduction and contrast for each microscope light source, observation method and type of sample, as well as custom settings, can be selected.

- Wafer/IC Circuit board
- Metal, Ceramic/Plastic
- Flat Panel Display

Using a desktop PC F D Br Ar



Image Stitching

Stitches together images acquired from multiple fields of view to create one image.





EDF (Extended Depth of Focus)

Create a single, all-in-focus image from images of differing focus.





Optical Interferometric Microscope Systems BW-S500/BW-D500 Series

Nikon's proprietary scanning-type optical interference measurement technology achieves 1 pm height resolution. Nikon offers variety application, lustrous surfaces, such as silicon wafer, glass and metallic deposition surfaces.

	High Speed Model	High Pixel Res	solution Model						
	BW-D500 Series	BW-S50	00 Series						
Height Resolution (algorithm)		1 pm							
Step Height Measurement Reproducibility	σ : 8 nm (8	σ: 8 nm (8 μm Step height measurement)							
Number of Pixels	510×510	2,046×2,046	1,022×1,022						
Height Measurement Time	2 s (10 µm scan)	19 s 8 s (10 µm scan) (10 µm scar							
Field of view	< 2,015×2,015 µm*	< 4,458×4,448 μm*							

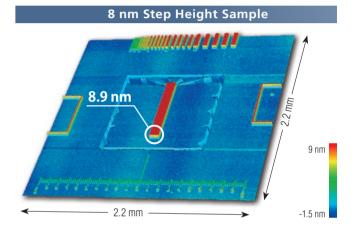




High Accuracy and Repeatability

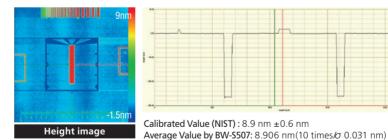
The BW-S500/BW-D500 series is calibrated by an 8 nm or 8 um VLSI Step Height Standards sample, certified by the NIST. Achieves extremely high accuracy and repeatability as a height measurement system.

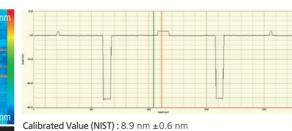


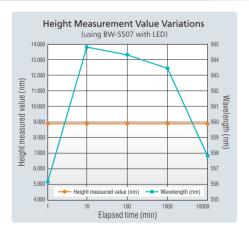


Measured value unsusceptible to variation of central wavelength of light source

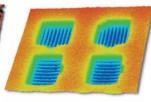
With Nikon's proprietary technology, measurement values with the BW-S500/ BW-D500 series are independent of central wavelength of light source. Measurements can be done immediately after switching on illumination source.

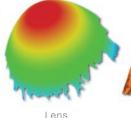


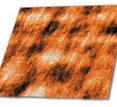


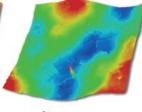












Polished ceramic surface Metal Etching Surface

Glass

Glossy paper

CFI60-2 / CFI60

Nikon's CFI60-2/CFI60 optical systems are highly evaluated for their unique concept of high NA combined with a long working distance. These lenses have been developed further and evolved achieving the apex in long working distance specifications, correct chromatic aberration, and an optimized lens weight.









NA: Numerical Aperture BF: Brightfield DF: Darkfield POL: Polarizing S-POL: Simple Polarizing DIC: Differential Interference Contrast UV-FL: UV Fluorescence FL: EPI Fluorescence

	Model	Magnification	NA	WD (mm)	BF	DF	POL	S-POL	DIC	UV-FL	FL
	T Plan EPI	1×	0.03	3.8	✓ ×				=		
	Plan (Semi-apochromat)	2.5×	0.075	6.5	~				<u>-</u>		
	TU Plan Fluor EPI	5×	0.15	23.5	V	_	_	~	∨ A	~	~
	Universal Plan Fluor (Semi-apochromat)	10×	0.3	17.5	~			~	✓ A	~	~
		20×	0.45	4.5	~		_	~	∨ A	~	~
		50×	0.8	1.0	~		<u>-</u>	~	✓ A	~	<u> </u>
		100×	0.9	1.0	V		_	~	✓ A	V	<u> </u>
	TU Plan Apo EPI	50×	0.8	2.0		_	_	~	∨ A	_	~
	Universal Plan Apo (Apochromat)	100×	0.9	2.0	~			~	✓ A	_	~
		150×	0.9	1.5	~	_	_	~	✓ A	_	~
	TU Plan Fluor EPI P	5×	0.15	23.5	~	_	~	~	∨ A	~	~
	Polarizing Universal Plan Fluor (Semi-apochromat)	10×	0.3	17.5	~		~	~	✓ A	~	~
		20×	0.45	4.5	~	_	~	~	∨ A	~	~
		50×	0.8	1.0	~		~	~	∨ A	~	~
		100×	0.9	1.0	~	_	~	~	∨ A	~	~
CEL. 2	TU Plan EPI ELWD	20×	0.4	19.0	~	_	_	~	∨B	_	~
CFI60-2	Long Working Distance Universal Plan (Semi-apochromat)	50×	0.6	11.0	~	_	_	~	∨B	_	~
	(Semi-apocnfornat)	100×	0.8	4.5	~			~	∨B		~
	T Plan EPI SLWD	10×	0.2	37.0	~	_	_	_			~
	Super Long Working Distance Plan	20×	0.3	30.0	~			_	_		~
	(Semi-apochromat)	50×	0.4	22.0	~	_		_	_	_	~
		100×	0.6	10.0	~			_			~
	TU Plan Fluor BD	5×	0.15	18.0	~	~	_	~	∨ A	~	~
	Universal Plan Fluor (Semi-apochromat)	10×	0.3	15.0	~	~		~	✓ A	/	~
		20×	0.45	4.5	~	~		~	∨ A		~
		50×	0.8	1.0	~	~		~	∨ A	V	~
		100×	0.9	1.0	~	~	_	~	∨ A	V	~
	TU Plan Apo BD	50×	0.8	2.0	V	~		~	∨ A		~
	Universal Plan Apo (Apochromat)	100×	0.9	2.0	~	~		~	∨ A		~
		150×	0.9	1.5	~	~	_	~	∨ A	_	~
	TU Plan BD ELWD	20×	0.4	19.0	~	~	_	~	∨B		~
	Long Working Distance Universal plan (Semi-apochromat)	50×	0.6	11.0	~	~		~	∨B	_	~
	(Gerin-apoeniornat)	100×	0.8	4.5	~	~	_	~	∨B	_	~
	L Plan EPI (Achromat)	40×	0.65	1.0	~	_	_	_	_	_	~
	LU Plan Apo EPI / Universal Plan Apo (Apochromat)	150×	0.95	0.3	~	_	_	~	∨ A	_	~
	L Plan EPI CR	20×	0.45	10.9–10.0	~						V
	LCD Substrate Inspection Plan (Achromat)	50×	0.7	3.9–3.0	~			_			~
	*Offers valid while supplies last	100×	0.85	1.2-0.85	~			_			V
		100×	0.85	1.3-0.95	~	_	_	_		_	~
	LE Plan EPI (Achromat)	5×	0.1	31	~			_			~
CFI ₆₀		10×	0.25	13	~					l	<u> </u>
		20×	0.4	3.6	~						~
		50×	0.75	0.5	~						~
		100×	0.9	0.31	~	_		_			~
	LE Plan BD (Achromat)	5×	0.1	18	~	<u> </u>				l	<u> </u>
		10×	0.25	13	~	~		_			~
		20×	0.4	3.6	~	~		_		_	V
		50×	0.75	0.5	V	~	_	_	_	_	V

^{✓ :} Available / = : Not available *A: Set prism position at A / B: Set prism position at B

For Incorporation into Microscopes

Modular Focusing Units

IM-4, LV-IM/LV-IMA, LV-FM/LV-FMA

Suitable for incorporating into systems, these focusing units enable the mounting of a universal illuminator and a motorized nosepiece.

	IM-4	LV-IM/LV-IMA	LV-FM/LV-FMA
Туре	Manual	Manual / Motorized	Manual / Motorized
Vertical Stroke	30 mm	30/20 mm	30/20 mm



Dynamic Auto-Focus Unit

LV-DAF

Hybrid Auto-focus features a wide focus range and fast tracking ability. A wide range of observation methods are supported, including brightfield, darkfield, and DIC. Reflective and transparent samples can both be observed.

*Not compatible with NIS-Elements imaging software

Detection System	Split Projection System/ Contrast Detection System
AF Light Source	Near Infrared LED (λ=770 nm)
Focal Time	within 0.7 sec (Obj. lens: 20×, Distance from focal position: 200 μm)
Observation	Brightfield, Darkfield, Polarizing, DIC



Compact Reflected Microscopes

CM Series

Ultra-compact reflected microscopes designed for integration into production lines to observe on monitors.



	CM-5A	CM-10A/CM-10L	CM-20A/CM-20L	CM-30A2/CM-30L2				
Camera Mount		C-mount (ENG-mo	unt possible with option)					
Tube Lens Magnification	— 1x 0.5x							
Compatible Objectives	A series: CF	FIC EPI Plan objectives / L se	eries: CFI60-2/ CFI60 EPI Plai	n objectives				
Illumination Optical System	k	Coehler illumination (high-qu	ality telecentric illumination	n)				
Attachment Surfaces	3 4							

Wafer Loaders

Nikon's proprietary technology ensures reliable loading of ultra-thin 100 µm wafers. The NWL 200 series achieve highly reliable loading, suitable for inspection of next-generation semiconductors.

	Diameter	ø200 mm / ø150 mm
Wafer	Thickness (standard)	300 um
	Thickness (option)	300–100 um
Surface	, back side macro inspection	✓

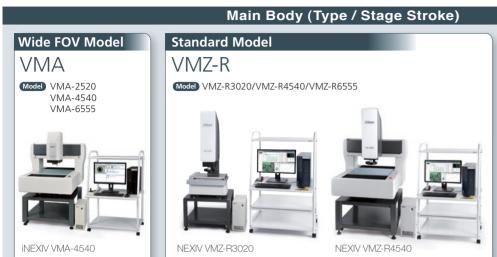


NWL200 Series

Please refer to individual product brochures for further details. Please refer to individual product brochures for further details.

Confocal NEXIV Series

Wide variety of stage strokes and magnifications are available for various customer requirements.



VMZ-H Model VMZ-H3030
NEXIV VMZ-H3030

High-precision Model

Model		Wide FOV			High-precision		
XY Stroke	250×200 mm	450×400 mm	650×550 mm	300×200 mm	450×400 mm	650×550 mm	300×300 mm
Wide FOV Head	✓	~	✓	✓	✓	✓	
Standard Head				~	✓	~	~
High-Magnification Head				~	✓	~	~
Z-axis Stroke	200 mm	200 mm	200 mm	200 mm	200 mm	200 mm	150 mm
Max. guaranteed loading capacity	15 kg	20 kg	30 kg	20 kg	40 kg	50 kg	30 kg
Maximum permissible error (Eux, Mpe Euy, Mpe)	2+8 <i>L</i> /1000 μm	2+6 <i>L</i> /10	000 μm		0.6+2 <i>L</i> /1000 μm		
Maximum permissible error (E∪z, MPE)	3+ <i>L</i> /50 μm	3+ <i>L</i> /10	00 μm		0.9+ <i>L</i> /150 μm		

Zoom Heads

Type A

Wide FOV and long working distance enables comfortable

operation. Laser AF and Touch Probe can be attached as optional accessories.

*Touch Probe is an option only for VMA series.

Type 1–4 Equipped with top,

bottom, and oblique ring

lights with adjustable angles. TTL (Through the Lens) Laser AF is a standard tool that can scan surfaces at 1000 points/second.

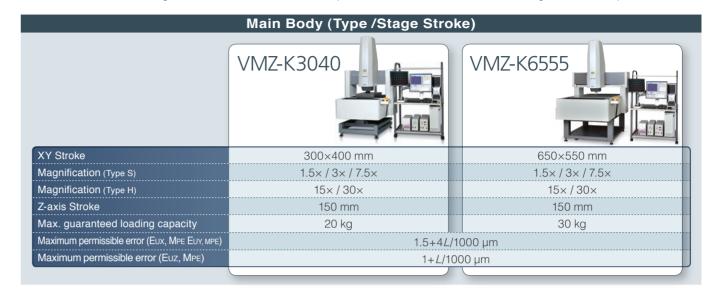
Type TZ

Equipped with 1-120x ultra high zoom ratio with 8 steps. Suitable for

measurements of small targets up to several micrometers.

FOV	W(mm)× D(mm)	13.3 10.0	9.33 7.01	7.8 5.8	4.7 3.5	2.6 1.9	2.33 1.75	1.33 1.00	1.165 0.875	0.622 0.467	0.582 0.437	0.311 0.233	0.291 0.218	0.155 0.117	0.146 0.109	0.070 0.068	0.073 0.055	0.039 0.029	WD
Wide FOV Head	Туре А	•		-	•	-		-											73.5 mm
Standard Head	Type 1		•		•		-		-	-									
	Type 2				•		-		-		-	-							50 mm
	Туре 3						•		-		-		-	-					
High-	Type 4								•		-		-		•	-			30 mm
Magnification Head	Type TZ				•		-		-	-			-		•		-	-	9.8 mm

Simultaneous wide-area height measurements with confocal optics and 2D measurement with 15x brightfield zoom optics.

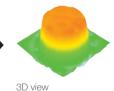


FOV	W(mm)× D(mm)	8 6	4 3	2.0 1.5	1.6 1.2	1.26 0.95	1.00 0.75	0.8 0.6	0.63 0.47	0.53 0.40	0.4 0.3	0.27 0.20	0.20 0.15	0.11 0.08	0.100 0.074	0.05 0.04	WD
Type S	1.5×	•	-	-			-			-							24mn
	3×		•	_			-			-		-					24mr
	7.5×				•			-			-		-	— •			5mr
Туре Н	15×					•		-			-		-		-		20mr
	30×								•		9		-		-	<u> </u>	5mr

Confocal NEXIV incorporates confocal optics for fast and accurate evaluation of fine three-dimensional geometries.

Confocal Optics are designed for wide FOV height measurement.

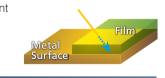


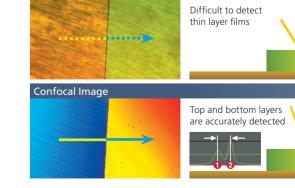


Thin Transparent Samples (Metal Surface Film / Semiconductor Resist)

Top layers of both thin transparent film and metal surface can be easily detected using Confocal optics.

Brightfield Image

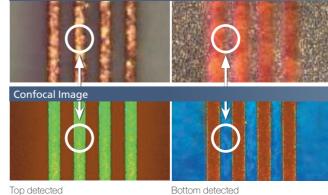




High Contrast and Multileveled Sample (PCBs)

Brightfield observation can sometimes be difficult due to blurred lines along sample structure. These lines can be clearly observed and measured using Confocal optics.





Please refer to individual product brochures for further details. Please refer to individual product brochures for further details.

Measuring Microscopes

Focused on high-precision and easy operability, a wide range of MM-products are available.



Basic Model MM-400

*

				-			
	50×50 mm / 5 kg	✓		✓	✓		
	100×100 mm / 15 kg	<u> </u>		V	V		
Stage Size/	150×100 mm / 15 kg	—		V	V		
Stage Size/ Loading Capacity 150×100 mm / 15 kg 200×150 mm / 20 kg 250×150 mm / 20 kg		—		—	<u> </u>		
		—		—	✓		
	300×200 mm / 20 kg	_		_	V		
Max. Sample	Height	110 mm		150 mm	200 mm		
Optical	Monocular	~		V	_		
Head	Binocular	_		~	✓		
X-Y-Z	2-axis	~		V	V		
X 1 Z	3-axis	_		V	V		
CCD		/ *		V	V		
Obj. Magnific	ation	1×/3×/5×/10×		1×/3×/5×/10×/	/20×/50×/100×		

*For simple video head only

✓ : Available / — : Not available

MM Type With Nikon's optical technology and highly precise stages, high-precision measurement can be achieved.

Universal Type

Offers a line-up compatible with dimensional measurement and various observation methods.



High-Precision Stages

The coarse/fine changeover lever and the RESET and SEND buttons are located near the X- and Y-axis knobs.







Y-axis Knob

Focusing Aid (FA)

The Split-Prism FA delivers sharp patterns to allow accurate focusing during Z-axis measurements.

FA patterns are clearly visible because they are split vertically







Profile Projectors

Nikon's profile projectors apply the principles of optics to the inspection of manufactured parts by projecting magnified silhouettes on a screen.



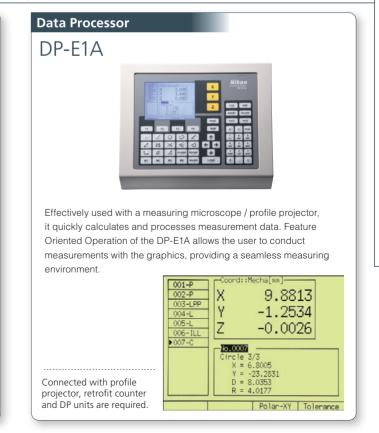
Large-Screer	n Model
V-20B	

	50×50 mm / 5 kg	✓	\checkmark				
	100×100 mm / 15 kg	✓	\checkmark				
Stage Size/ Loading Capacity 150×100 mm / 15 kg 200×150 mm / 20 kg 250×150 mm / 20 kg		✓	✓				
		✓	✓				
		✓	\checkmark				
Max. Sample	e Height	100 mm*²	150 mm				
Screen		305 mm	500 mm				
Image		Erect	Inverted				
Projection	Magnification	5×/10×/20×/25×/50×/100×/200×	5×/10×/20×/50×/100×				
Lens	FOV (with 10× lens)*1	30.5 mm	50 mm				
Digital Protra	actor	✓	✓				
Digital Coun	ter	V	\checkmark				

*1: Actual FOV = Effective diameter of screen / Lens magnification *2: Maximum sample height is 70 mm when 200×150 mm stage is installed. ✓ : Available / — : Not available

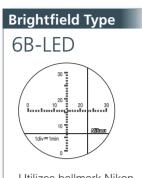
Data Processing Systems for Measuring Microscopes and Profile Projectors





Autocollimators

Autocollimator is an easy-to-use but precise metrology instrument for angularity, parallelism, perpendicularity, straightness of precision components machine guideway and many other applications.



Utilizes hallmark Nikon optics to illuminate surface details.

Darkfield Type



Optimal for measuring small, flat mirrors.



Observation Method	6B-LED: Brightfield, 6D-LED: Darkfield
Readout System	Adjustment in viewfield and reading on micrometer
Measuring Range	30 minutes of arc (both vertical and horizontal axes)
Minimum Range	0.5 seconds of arc

Plane Mirror C

Both sides are perfectly parallel, permitting its use as a reference for non-reflective surface. Also useful for measuring extremely small angles where a smaller mirror is desirable. *Wooden case provided.



	Outer Diameter	30 mm
	Thickness	12 mm
	Parallelism	2 seconds of arc

LED Illuminator AC-L1

LED illumination unit for retrofitting onto Autocollimator 6B/6D illumination unit.



Power Source

AA batteries×2, AC adaptor

DIGIMICRO

With built-in photoelectric digital length measuring systems, DIGIMICRO offers flawless contact measurements of dimension, thickness, and depth.







Main Unit	MF-1001	MF-501	MH-15M
Measuring Range	0–100 mm	0–50 mm	0–15 mm
Accuracy (20°C)	3 μm	1 μm	0.7 μm
Measuring Force	Downward direction 1.225 to 1.813N (variable to about 0.441N), lateral 0.637 to 1.225N	Downward direction 1.127 to 1.617N (variable to about 0.294N), lateral 0.637 to 1.225N	Upward direction 0.245N, downward 0.637N, lateral 0.441N *With lifting release
Operating Temperature	0 to 40°C		

Stand MS-21

Optical Flat / Optical Parallel / Standard 300 mm Scale

Optical Flat

The optical flat is used to check the flatness level of a surface provided with mirror-smooth finish.

Flatness level can be measured by observing interference fringes by placing the optical flat in contact with the sample.





Diameter	Glass (ø60 mm)	Glass (ø130 mm)
Thickness	15 mm	27 mm
Flatness	0.1 μm	0.1 μm

Optical Parallel

Both planes of the optical parallel have been precisely finished flat and parallel.

It is used to check the flatness and parallel levels of a sample by observing

interference fringes by placing the optical parallel in contact with the sample.

	eague.	
eter	30 mm	
ness	12 mm / 12.12 mm / 12.25 mm / 12.37 mm	
ss	within 0.1 μm	
elism	within 0.2 μm	

15

Standard 300mm Scale

Gauges stage travel accuracy up to 300 mm. Both 10 mminterval sensor patterns and calibrations are provided. Made of the glass with low coefficient of thermal expansion, for minimizing thermal influence.

*Within 1 µm against compensation values.

Please refer to individual product brochures for further details. Please refer to individual product brochures for further details.

^{*}Optical flats and parallels with greater precision are available by custom orders.

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TO ENSURE CORRECT USAGE, READ THE CORRESPONDING MANUALS CAREFULLY BEFORE USING THE EQUIPMENT.



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